

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :  
Kenji KAMIMURA et al. : Attn: BOX PCT  
Serial No. NEW : Docket No. 2001-0076A  
Filed March 14, 2001 :

POLISHING APPARATUS  
[Corresponding to PCT/JP01/00382  
Filed January 22, 2001]

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

Prior to examination of the above-referenced U.S. patent application please amend the application as follows:

IN THE CLAIMS

Please amend the claims as follows:

A1 1. (Amended) A polishing apparatus with a polishing table having a polishing surface and a top ring for pressing a workpiece to be polished at a predetermined pressure with interposing said workpiece between said polishing table and said top ring to polish said workpiece, said polishing apparatus comprising:  
at least two dressing units for dressing said polishing surface by being brought into contact with said polishing surface.

A2 3. (Amended) A polishing apparatus according to claim 1, wherein: